

# Patent Assignment Abstract of Title

**Total Assignments: 1**
**Application #:** 10043190 **Filing Dt:** 01/14/2002

**Patent #:** NONE

**Issue Dt:**
**PCT #:** NONE

**Publication #:** 20020096188
**Pub Dt:** 07/25/2002

**Inventor:** Hiroshi Nogami

**Title:** Method of cleaning CVD device

**Assignment: 1**
**Reel/Frame:** 012473/0209 **Received:** 01/22/2002

**Recorded:**  
01/14/2002

**Mailed:**  
03/13/2002

**Pages:**  
**Conveyance:** ASSIGNMENT OF ASSIGNORS INTEREST (SEE DOCUMENT FOR DETAILS).

**Assignor:** NOGAMI, HIROSHI
**Exec Dt:** 01/11/2002

**Assignee:** ANELVA CORPORATION

 5-8-1 YOTSUYA, FUCHU-SHI  
 TOKYO 183, JAPAN

**C rrespondent:** BURNS, DOANE, SWECKER & MATHIS, L.L.P.

 PLATON N. MANDROS  
 P.O. BOX 1404  
 ALEXANDRIA, VIRGINIA 22313-1404

Search Results as of: 6/13/2003 1:55:32 P.M.

---

If you have any comments or questions concerning the data displayed, contact OPR / Assignments at 703-308-9723  
 Web interface last modified: Oct. 5, 2002

## WEST Search History

DATE: Friday, June 13, 2003

<u>Set Name</u>	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u>
		result set	
<i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR=YES; OP=ADJ</i>			
L9	L6 and (He or Ar or Ne or Kr or Xe)	63	L9
L8	L6 same (He or Ar or Ne or Kr or Xe)	6	L8
L7	L6 and 15	62	L7
L6	(CVD or chamber or vessel) same clean\$3 same (oxygen with fluor\$3) ((134/1.1  134/21  134/22.1 )!.CCLS.  (216/63  216/64  216/67	206	L6
L5	!).CCLS.  (204/298.01 )!.CCLS.  (438/905 )!.CCLS.  (156/345.29  156/345.35  156/345.47 )!.CCLS. )	5149	L5
<i>DB=JPAB,EPAB,DWPI; PLUR=YES; OP=ADJ</i>			
L4	L1 and chemical vapor deposition	0	L4
L3	L1 and clean\$3	5	L3
L2	L1 and CVD	0	L2
L1	nogami-hiroshi\$.in.	108	L1

END OF SEARCH HISTORY